

AMENDMENTS TO THE CLAIMS

Please enter the following amendments:

1. (Currently Amended) A method of manufacturing a plasma display panel, in which a plurality of structure structures of the plasma display panel [[is]] are formed with photolithography, wherein at least one of the structures of the plasma display panel is exposed twice ~~in a process of forming the structure~~ using successive first and second exposures, and a photomask ~~and the plasma display panel are~~ [[is]] moved relative to each other within an allowable range of displacement in [[a]] an exposure pattern, between [[a]] the first and [[a]] second exposures.

2. (Currently Amended) A method of manufacturing a plasma display panel, in which a plurality of structure structures of the plasma display panel [[is]] are formed with photolithography, wherein at least one of the structures of the plasma display panel is exposed twice ~~in a process of forming the structure~~ using successive first and second exposures, and a photomask ~~and the plasma display panel are~~ [[is]] moved relative to each other by ~~at least one~~ eyele multiple cycles of periodicity included in [[a]] an exposure pattern, and also within an allowable range of displacement at the position, between [[a]] the first and [[a]] second exposures.

3. (New) The method according to claim 1, wherein each of the structures which is exposed twice extends primarily in a lengthwise direction, has a width w in a widthwise direction orthogonal to the lengthwise direction, and is disposed periodically with a pitch p.

4. (New) The method according to claim 3, wherein the photomask is moved a distance in the widthwise direction between the first and second exposures, the distance being less than w .

5. (New) The method according to claim 3, wherein the photomask is moved two or more integral times the distance p in the widthwise direction between the first and second exposures.

6. (New) The method according to claim 3, wherein the photomask is moved a distance in the lengthwise direction between the first and second exposures, the distance being less than p .

7. (New) The method according to claim 3, wherein the photomask is moved a distance in the lengthwise direction between the first and second exposures, the distance being less than w .

8. (New) The method according to claim 4, wherein the structures are address electrodes formed by exposing a photosensitive silver paste.

9. (New) The method according to claim 5, wherein the structures are address electrodes formed by exposing a photosensitive silver paste.

10. (New) The method according to claim 6, wherein the structures are address electrodes formed by exposing a photosensitive silver paste.

11. (New) The method according to claim 7, wherein the structures are address electrodes formed by exposing a photosensitive silver paste.